

(19)  
(12)

(KR)  
(B1)

(51) 。 Int. Cl. <sup>6</sup>  
H01L 21/28

(45)  
(11)  
(24)

2002 05 13  
10 - 0324020  
2002 01 29

(21) 10 - 1998 - 0035019  
(22) 1998 08 27

(65) 2000 - 0015238  
(43) 2000 03 15

(73)

136 - 1

(72)

105 - 907

(74)

:

(54)

1 , 2 가 , 1 2 , 2  
가 .

도 2c

1a 1d

2a 2c

11,21 : 13,23 : 1

15,25 : 17 : 2

19,27 :

가 (Al) 가 ( Physical Vapor Deposition, PVD )  
 가 ( chemical vapor deposition, CVD )

가 ( chemical vapor deposition, CVD )

1a 1d

(21) (23) (25)  
 (25) TiN ( 1a, 1b)

(27) (25) (25)  
 (27) MOCVD

(27) 2000 ( sub micron )  
 가 (27)

WN , , MOCVD 가 TiN  
 MOCVD . ( 1c, 1d)

ylidichlorosilane ) , DMDCS ( dimeth

1 , ,  
 1 , ,  
 2 가 , , 2

2a 2c .  
 (15) (11) 1 (13) TiN (15)  
 (15) (15) ( )  
 (15) 2 (17)  
 ( 2a)  
 ( 2b) 2 (17) (15)  
 가 2 (17)

, MOCVD (15) (19) .  
 , (19) (15) , 2 (19) (17)  
 (19) , ( 2c)  
 , (11) , (11)

가 . , 가

(57)

1.

1 ,

1 ,

2 가 , 2

2.

1 ,

1 2 .

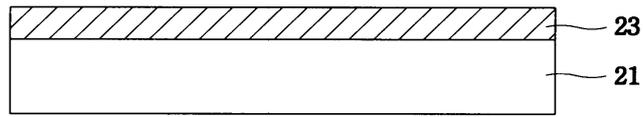
3.

1 ,  
 TiN WN .

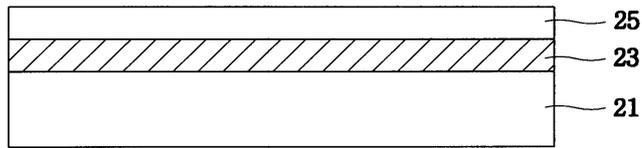
4.

1 ,  
 MOCVD

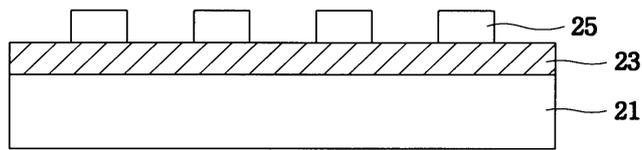
1a



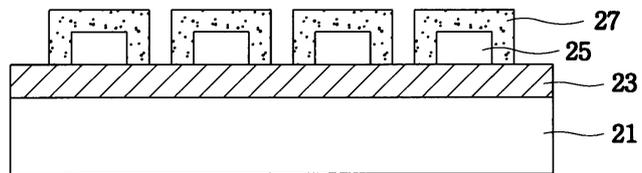
1b



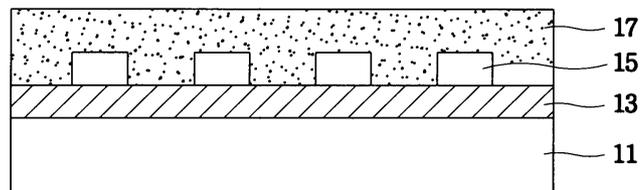
1c



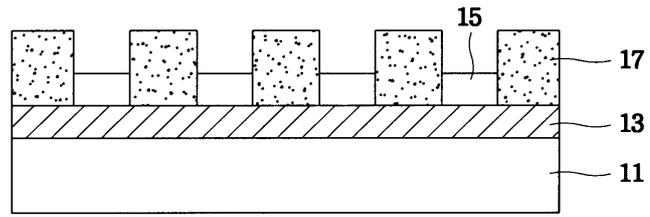
1d



2a



2b



2c

